

# Thermal Oxide Furnace

- MRL Thermal Oxide Furnace is located in the Class-1000 cleanroom.
- It is designed to grow  $\text{SiO}_2$  (silicon dioxide) at high temperatures from  $800^\circ\text{C}$  –  $1200^\circ\text{C}$  using either a wet or dry growth method.
- It is often used in semiconductor devices for dielectric insulating thin films, field oxides, and gate oxides.

